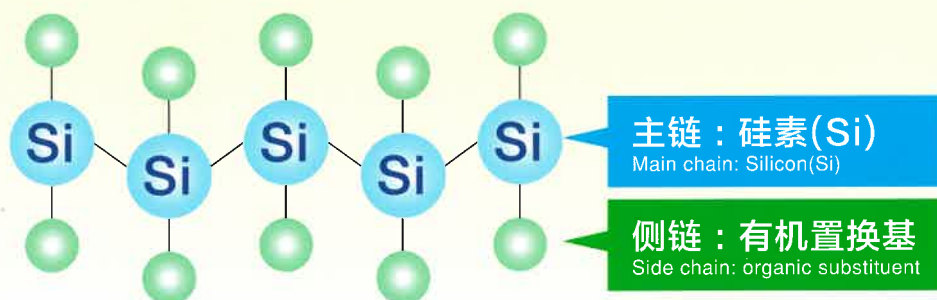


以Si-Si结合为主框架 拥有光反应性及高折射率,高耐热等特色
适用于镀膜或图案化用途

Has Si-Si bonds in the main skeleton, photoreactive and high refractive index, since it has features such as high heat resistance, it is suitable for coating and patterning applications.

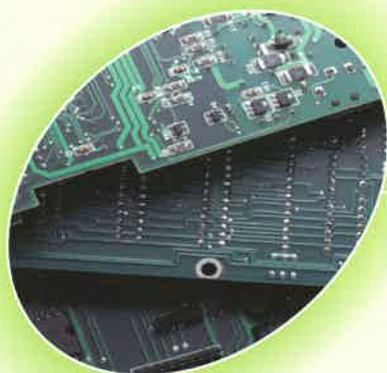
【光反应材料 · 光图案化材料的特色】

Features of the photoreactive materials and photo patterning materials



- 光反应性
Photoreactive
- 高折射率
High refractive index
- 高耐热性
High heat resistance
- 低介电常数
Low dielectric constant
- 高拒水性
High water repellency
- 高Si含有
High Si content

用途例 / Application Examples



电子部品
Electronic parts



显示器
Display

■ 各种光刻胶 · 镀膜剂用途 Various resist coating applications

- 用于光阻材料的图案化剂(高折射率,高耐热性,透明性,显像性)
Photoresist for patterning (High refractive index, High heat resistance, Transparency, Developable)
- 用于ITO薄膜的涂层剂(高折射率,透明性)
ITO film for coating (High refractive index, Transparency)
- 用于夹层绝缘膜的涂层剂(低介电常数)
Interlayer insulating film for coating (Low dielectric constant)
- 用于彩色滤光片的涂层剂(高折射率,高耐热)
Color filter for coating (High refractive index, High heat resistance)

■ 变性用原材料用途 Denaturation for raw materials applications

- 用于反射防止膜的反应起始剂
Antireflection film for the initiator (Photoreactive, High refractive index)

也可用于树脂改性用途
You can use it in resin modification applications.

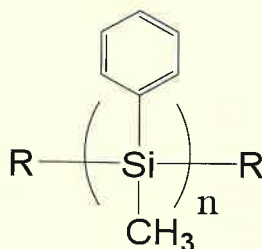
代理商：松金国际贸易南通有限公司

联系电话：13390981305 公司网站：www.matsukanechem.com

光反应性材料 OGSOL SI-10

Photoreactive materials OGSOL SI-10

构造 / Structure



OGSOL SI-10-10
OGSOL SI-10-20

外观：淡黄色粉末
Appearance: Light yellow powder

物性表 / Physical Properties Table

		OGSOL SI-10-10	OGSOL SI-10-20
分子量 Molecular weight ※GPC(聚苯乙烯换算)	Mn	2,100	1,100
	Mw	12,700	1,800
耐热性(5%重量减) Heat resistance(5% weight reduction)	℃	362	350
折射率(589nm) Refractive index(589nm)	—	1.67	1.68

溶剂溶解性 Solvent solubility

评价条件：制成10wt%溶液 使用振动机使之溶解

Assessment Condition: Solubility to each solvent was assessed using a shaker at room temperature.

评价方法(目视)：O1小时内溶解、X不溶

Evaluation method: 10wt% solution was obtained at 1 hour (O) or not (X).

	聚醚 Ethers	芳香族 Aromatic series	聚酯 Ester	酮 Ketones			酒精 Alcohol	
	THF	甲苯 Toluene	PGMEA	环己酮 Cyclohexanone	MEK	MIBK	i-丙醇 i-Propanol	PGME
OGSOL SI-10-10	O	O	O	O	O	O	X	X
OGSOL SI-10-20	O	O	O	O	O	X	X	X

特长 / Features

- 光反应性
Photoreactive
- 高折射率
High refractive index
- 高耐热性
High heat resistance
- 树脂改性剂
Resin modifier

用途例 / Application Example

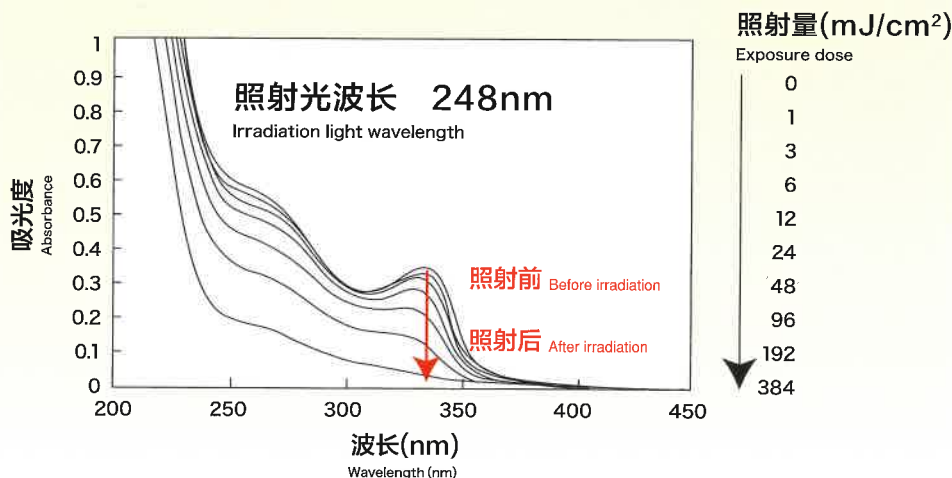
- 涂层
Coating
- 光反应剂
Photoreactive
- 图案化
Patterning

通过紫外线照射吸收后光谱变化 /

Absorption Spectrum Change by Ultraviolet Irradiation

在192mJ/cm²区段Si-Si结合断开, 达到图案化
(340nm : Si-Si结合的吸收光谱)

The Si-Si bonds are cut off at 192 mJ/cm², and enables patterning.
(Absorption spectrum of Si-Si bonds: 340nm)



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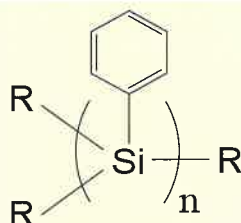
光成像材料 OGSOL SI-20

Photo patterning materials OGSOL SI-20

SI-20用于光阻材料,可制成高折射率且透明涂层

By using the SI-20 in a resist material, high refractive index and a transparent coating layer can be produced.

构造 / Structure



OGSOL SI-20-10

外观: 淡黄色粉末

Appearance: Light yellow powder

物性表 / Physical Properties Table

		OGSOL SI-20-10
分子量 Molecular weight ※GPC(聚苯乙烯换算)	Mn	900
	Mw	1,200
耐热性(5%重量减) Heat resistance (5% weight reduction)	℃	347
折射率(589nm) Refractive index	—	1.64

溶剂溶解性 Solvent solubility

评价条件: 制成10wt%溶液 使用振动机使之溶解

Assessment Condition: Solubility to each solvent was assessed using a shaker at room temperature.

评价方法(目视): O1小时内溶解, X不溶

Evaluation method: 10wt% solution was obtained at 1 hour (○) or not (X).

	聚醚 Ethers	芳香族 Aromatic series	聚脂 Ester	酮 Ketones			酒精 Alcohol	
	THF	甲苯 Toluene	PGMEA	环己酮 Cyclohexanone	MEK	MIBK	i-丙醇 i-Propanol	PGME
OGSOL SI-20-10	○	○	○	○	○	×	×	○

特长 / Features

- 光反应性
Photoreactive
- 高反射率
High refractive index
- 高耐热性
High heat resistance
- 低诱电率
Low dielectric constant

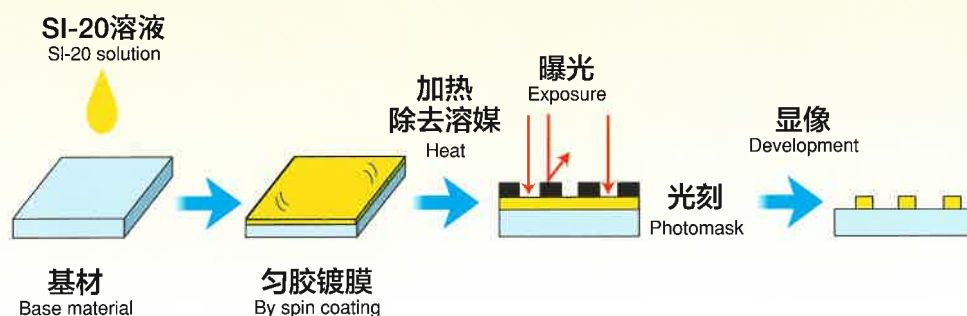
用途例 / Application Example

- 光刻胶
Resist
- 图案化
Patterning
- 镀膜
Coating

光刻胶示意图 / Resist image diagram

将溶解后的SI-20涂于溶剂上
通过曝光成像达到图案化

The SI-20 which was dissolved in a solvent is applied, it is possible to be developed after being exposed, the pattern can be produced.



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